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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/520,815	01/07/2005	Kohshi Taguchi	2691-000013/US	2951	
30593 7	590 09/30/2005		EXAM	EXAMINER	
•	DICKEY & PIERCE, P	ABRAMOWITZ	ABRAMOWITZ, HOWARD E		
P.O. BOX 891 RESTON, VA	-		ART UNIT	ART UNIT PAPER NUMBER	
			1762		
		•			

DATE MAILED: 09/30/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

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•	Application No.	Applicant(s)	
	10/520,815	TAGUCHI ET AL.	
Office Action Summary	Examiner	Art Unit	
· · · · · · · · · · · · · · · · · · ·	Howard E. Abramowitz	1762	
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the c	orrespondence add	ress
A SHORTENED STATUTORY PERIOD FOR REPLY WHICHEVER IS LONGER, FROM THE MAILING D/ Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication.  If NO period for reply is specified above, the maximum statutory period v Failure to reply within the set or extended period for reply will, by statute Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION 36(a). In no event, however, may a reply be tin vill apply and will expire SIX (6) MONTHS from 1, cause the application to become ABANDONE	N. nely filed the mailing date of this com D (35 U.S.C. § 133).	•
Status			•
1)⊠ Responsive to communication(s) filed on <u>07 Ja</u>	anuary 2005.		
	action is non-final.		
3) Since this application is in condition for allowar	nce except for formal matters, pro	secution as to the r	merits is
closed in accordance with the practice under E	x parte Quayle, 1935 C.D. 11, 45	53 O.G. 213.	
Disposition of Claims			
4) ☐ Claim(s) 1-14 is/are pending in the application. 4a) Of the above claim(s) is/are withdray 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1-14 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and/or	vn from consideration.		
Application Papers			
9) ☐ The specification is objected to by the Examine 10) ☑ The drawing(s) filed on <u>07 January 2005</u> is/are: Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct 11) ☐ The oath or declaration is objected to by the Ex	a) $\square$ accepted or b) $\square$ objected drawing(s) be held in abeyance. See ion is required if the drawing(s) is object.	e 37 CFR 1.85(a). jected to. See 37 CFF	R 1.121(d).
Priority under 35 U.S.C. § 119			
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of:  1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the prior application from the International Bureau * See the attached detailed Office action for a list	s have been received. s have been received in Applicati rity documents have been receive u (PCT Rule 17.2(a)).	on No ed in this National S	itage
Attachment(s)  1) Notice of References Cited (PTO-892)  2) Notice of Draftsperson's Patent Drawing Review (PTO-948)  3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)  Paper No(s)/Mail Date 2/22/05,1/7/05.	4) Interview Summary Paper No(s)/Mail Da 5) Notice of Informal P 6) Other:	ate	152)

## DETAILED ACTION

### Claim Observations

Claim 2 recites that the substrate "is heated to room temperature to 800 °C" this is awkwardly worded however the examiner will take "room temperature to 800 °C" to be a range of temperatures.

#### Claim Rejections - 35 USC § 102

Claims 1-4 and 9-11 are rejected under 35 U.S.C. 102(b) as being anticipated by Japanese patent No. 2000-212747 A ('747).

Referring to claims 1, 3 and 9, '747 discloses a method for forming a silicon nitride film comprising: accommodating a substrate in an internal space of a chamber (abstract), supplying hexamethyldisilazane gas and a nitrogen compound that is plasma excited to the chamber accommodating the substrate (abstract), depositing a reaction product of the hexamethyldisilazane and the gas including a nitrogen compound that is plasma excited on the substrate to form a silicon nitride film (abstract).

Referring to claim 2, '747 discloses that the substrate is heated to 300 °C (paragraph 28).

Referring to claims 4, 10 and 11 '747 discloses that the nitrogen compound is nitrogen gas (abstract).

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Claims 5-8 and 12-14 are rejected under 35 U.S.C. 102(b) as being anticipated by Tsu et al. (Physical Review volume 33 number 10 pp. 7069-7076).

Referring to claims 5-8 and 12-14, Tsu et al. discloses an apparatus for forming a silicon nitride film on the surface of the substrate, comprising: a chamber in which the substrate is accommodated in its internal space; a first supplying means for supplying hexamethyldisilazane gas to the internal space of the chamber; a second gas supplying means for supplying gas including a nitrogen compound (ammonia or nitrogen gas) to the internal space of the chamber; and plasma excitation means that is provided in the second gas supplying means, for plasma exciting the gas including a nitrogen compound supplied to the internal space of the chamber. A heater is provided on the substrate support (figure 1).

While the first supplying means in Tsu et al. is used for silane and not hexamethyldisilazane "It is well settled that the intended uses of and the particular material used in a coating apparatus have no significance in determining patentability of apparatus claims." *Ex parte Thibault*, 164 U.S.P.Q. 666 (Bd. Pat. App. 1969).

#### Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Howard E. Abramowitz whose telephone number is 571-272-8557. The examiner can normally be reached on monday-friday 9:00-5:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Timothy H. Meeks can be reached on 571-272-1423. The fax phone

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number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

TIMOTHY MEEKS
UPERVISORY PATENT EXAMINER

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